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L3 ANSWER 6 OF 7 CAPLUS COPYRIGHT 2003 ACS

AN 1997:533759 CAPLUS

DN 127:141981

TI Electrodeposition solution for forming tin and tin-lead alloy

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SO Jpn. Kokai Tokkyo Koho, 4 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

IC ICM C25D003-32

ICS C25D003-56

CC 72-8 (Electrochemistry)

Section cross-reference(s): 56

FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 09184087	A2	19970715	JP 1995-343115	19951228
PRAI	JP 1995-343115		19951228		

OS MARPAT 127:141981

AB The title aq. soln. contains an org. sulfonic acid, a Sn²⁺ salt of an org.

sulfonic acid (and optionally a Pb²⁺ salt of an org. sulfonic acid), polyoxyethylene alkylphenyl ether or polyoxyethylene naphthyl ether as a dispersing agent, and **chlorobenzaldehyde**, naphthaldehyde, and paraacetaldehyde as a brightener. A bright Sn alloy and Sn-Pb alloy can be plated at wide c.d. region.

ST tin electrodeposition bath; lead tin alloy electroplating bath

IT Electrodeposition

(electrodeposition bath for tin and tin-lead alloy)

IT 123-63-7, Paracetaldehyde 30678-61-6, Naphthaldehyde 35913-09-8,

Chlorobenzaldehyde

RL: TEM (Technical or engineered material use); USES (Uses)

(brightener; in electrodeposition bath for tin and tin-lead alloy)

IT 9016-45-9, Polyethylene oxide nonylphenyl ether 69778-08-1,

Polyethylene

oxide mononaphthyl ether

RL: MOA (Modifier or additive use); TEM (Technical or engineered material use); USES (Uses)

(dispersing agent; in electrodeposition bath for tin and tin-lead alloy)

IT 75-75-2, Methanesulfonic acid 95860-12-1, **Lead**

methanesulfonate 95860-13-2, **Tin**

methanesulfonate

RL: TEM (Technical or engineered material use); USES (Uses)

(in electrodeposition bath for tin and tin-lead alloy)